

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	"6880561".pn.	US-PGPUB; USPAT	OR	ON	2007/11/14 09:22
L2	1155	134/22.1.ccls.	US-PGPUB; USPAT	OR	ON	2007/11/14 09:22
L3	826	134/22.18.ccls.	US-PGPUB; USPAT	OR	ON	2007/11/14 09:22
L4	2150	134/42.ccls.	US-PGPUB; USPAT	OR	ON	2007/11/14 09:22
L5	357	438/905.ccls.	US-PGPUB; USPAT	OR	ON	2007/11/14 09:22
S8	1	"5685951".pn.	US-PGPUB; USPAT	OR	ON	2007/10/10 10:12
S10	344	((silicon adj dioxide) or (SiO2 or SiOx or SiOn or "SiO.sub2" or "SiO.subx" or "SiO.subn" or "SiO.sub.2" or "SiO.sub.x" or "SiO.sub.n")) same (ammonia or (NH3 or NHx or NHHH or NHsubx or NHsubNH or "NH.subx" or "NH.subNH" or "NH.sub.x" or "NH.sub.NH")) and (TEOS (tetraethyl adj orthosilicate)) and (clean\$4 remov\$4 treat\$4) and (HF or (hydrofloric adj acid) or (hydrogen adj flouride))	US-PGPUB; USPAT	OR	ON	2007/11/13 17:13
S11	250	((silicon adj dioxide) or (SiO2 or SiOx or SiOn or "SiO.sub2" or "SiO.subx" or "SiO.subn" or "SiO.sub.2" or "SiO.sub.x" or "SiO.sub.n")) same (ammonia or (NH3 or NHx or NHHH or NHsubx or NHsubNH or "NH.subx" or "NH.subNH" or "NH.sub.x" or "NH.sub.NH")) and (TEOS (tetraethyl adj orthosilicate)) and (clean\$4 remov\$4 treat\$4) and (HF or (hydrofloric adj acid) or (hydrogen adj flouride)) and (semiconductor wafer substrate) and temperature and pressure and time	US-PGPUB; USPAT	OR	ON	2007/10/09 11:23

## EAST Search History

S12	8	((silicon adj dioxide) or (SiO2 or SiOx or SiOn or "SiO.sub2" or "SiO.subx" or "SiO.subn" or "SiO.sub.2" or "SiO.sub.x" or "SiO.sub.n")) same (ammonia or (NH3 or NHx or NHNH or NHsubx or NHsubNH or "NH.subx" or "NH.subNH" or "NH.sub.x" or "NH.sub.NH")) same (TEOS (tetraethyl adj orthosilicate)) same (clean\$4 remov\$4 treat\$4) same (HF or (hydrofloric adj acid) or (hydrogen adj flouride)) and (semiconductor wafer substrate) and temperature and pressure and time	US-PGPUB; USPAT	OR	ON	2007/10/09 12:18
S13	0	134/22.1.clas.	US-PGPUB; USPAT	OR	ON	2007/10/09 12:18
S14	1142	134/22.1.ccls.	US-PGPUB; USPAT	OR	ON	2007/10/09 12:19
S15	0	134/22.1.ccls. and teos and temperature and time and pressure and ((HF or (hydrofloric adj acid) or (hydrogen adj flouride)) same ammonia or (NH3 or NHx or NHNH or NHsubx or NHsubNH or "NH.subx" or "NH.subNH" or "NH.sub.x" or "NH.sub.NH")) near (vapor gas)	US-PGPUB; USPAT	OR	ON	2007/11/13 15:28
S16	1	2004/0091813	US-PGPUB; USPAT	OR	ON	2007/10/10 10:13
S17	1	"20040091813"	US-PGPUB; USPAT	OR	ON	2007/10/10 10:13
S18	34	teos and temperature and time and pressure and ((HF or (hydrofloric adj acid) or (hydrogen adj flouride)) same ammonia or (NH3 or NHx or NHNH or NHsubx or NHsubNH or "NH.subx" or "NH.subNH" or "NH.sub.x" or "NH.sub.NH")) near (vapor gas)	US-PGPUB; USPAT	OR	ON	2007/11/13 15:29
S19	40	teos and temperature and (time second minute) and pressure and ((HF or (hydrofloric adj acid) or (hydrogen adj flouride)) same ammonia or (NH3 or NHx or NHNH or NHsubx or NHsubNH or "NH.subx" or "NH.subNH" or "NH.sub.x" or "NH.sub.NH")) near (vapor gas)	US-PGPUB; USPAT	OR	ON	2007/11/13 15:30

## EAST Search History

S20	15	("20020011210"   "20030015798"   "5252178"   "5281302"   "5356478"   "5756400"   "6187691"   "6271148"   "6329297"   "6347636"   "6352945"   "6374831"   "6383955"   "6387207"   "6569257").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2007/11/13 15:48
S21	342	((silicon adj dioxide) or (SiO2 or SiOx or SiOn or "SiO.sub2" or "SiO.subx" or "SiO.subn" or "SiO.sub.2" or "SiO.sub.x" or "SiO.sub.n")) same (ammonia or (NH3 or NHx or NHHH or NHsubx or NHsubNH or "NH.subx" or "NH.subNH" or "NH.sub.x" or "NH.sub.NH")) and (TEOS (tetraethyl adj orthosilicate)) and (clean\$4 remov\$4 treat\$4) and (HF or (hydrofloric adj acid) or (hydrogen adj flouride)) and (time seconds minutes)	US-PGPUB; USPAT	OR	ON	2007/11/13 16:11
S22	38	((silicon adj dioxide) or (SiO2 or SiOx or SiOn or "SiO.sub2" or "SiO.subx" or "SiO.subn" or "SiO.sub.2" or "SiO.sub.x" or "SiO.sub.n")) same (ammonia or (NH3 or NHx or NHHH or NHsubx or NHsubNH or "NH.subx" or "NH.subNH" or "NH.sub.x" or "NH.sub.NH")) and (TEOS (tetraethyl adj orthosilicate)) and (clean\$4 remov\$4 treat\$4) and (HF or (hydrofloric adj acid) or (hydrogen adj flouride)) and (time seconds minutes) and (clean\$4 etch\$4 remov\$4).ti.	US-PGPUB; USPAT	OR	ON	2007/11/13 16:51
S23	15	("20020011210"   "20030015798"   "5252178"   "5281302"   "5356478"   "5756400"   "6187691"   "6271148"   "6329297"   "6347636"   "6352945"   "6374831"   "6383955"   "6387207"   "6569257").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2007/11/13 16:45

## EAST Search History

S24	226	((silicon adj dioxide) or (SiO2 or SiOx or SiOn or "SiO.sub2" or "SiO.subx" or "SiO.subn" or "SiO.sub.2" or "SiO.sub.x" or "SiO.sub.n")) same (ammonia or (NH3 or NHx or NHNH or NHsubx or NHsubNH or "NH.subx" or "NH.subNH" or "NH.sub.x" or "NH.sub.NH")) and (clean\$4 remov\$4 treat\$4) and (HF or (hydrofloric adj acid) or (hydrogen adj flouride)) and (time seconds minutes) and (clean\$4 etch\$4 remov\$4).ti.	US-PGPUB; USPAT	OR	ON	2007/11/13 17:01
S25	1	"6165956".pn.	US-PGPUB; USPAT	OR	ON	2007/11/13 17:01
S26	23	minimize adj time same (semiconductor wafer substrate) with clean\$4	US-PGPUB; USPAT	OR	ON	2007/11/14 08:49